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# Ion chemistry in boron trichloride BCl<sub>3</sub>

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#### **Abstract**

Ionization of boron trichloride by electron impact has been examined by Fourier transform mass spectrometry. The parent ion, BCl<sub>3</sub><sup>+</sup>, and three fragment ions, BCl<sub>2</sub><sup>+</sup>, BCl<sub>2</sub><sup>+</sup>, and Cl<sub>3</sub><sup>+</sup>, are observed. The total ionization cross section is  $1.0 \pm 0.1 \times 10^{-15}$  cm<sup>2</sup> between 30 and 60 eV. BCl<sub>3</sub><sup>+</sup> and Cl<sub>3</sub><sup>+</sup> react with neutral BCl<sub>3</sub> to yield BCl<sub>2</sub><sup>+</sup> with bimolecular rates of  $5.3 \pm 0.5 \times 10^{-10}$  cm<sup>3</sup> s<sup>-1</sup> and  $6.2 \pm 0.5 \times 10^{-10}$  cm<sup>3</sup> s<sup>-1</sup>, respectively. BCl<sub>2</sub><sup>+</sup> does not react with BCl<sub>3</sub>. Cl<sup>-</sup> and Cl<sub>2</sub><sup>-</sup> are produced by dissociative attachment of low-energy electrons to BCl<sub>3</sub>, and Cl<sub>2</sub><sup>-</sup> is found to rapidly react with BCl<sub>3</sub> to form BCl<sub>4</sub><sup>-</sup>.

## 1. Introduction

Boron trichloride (BCl<sub>3</sub>) is used in plasmas for etching of semiconductors [1-3], deposition or doping of boron [4,5], and in situ electric field measurements [25]. Literature reports on its electron impact ionization [7,8], attachment [9,10], scattering [11], dissociation kinetics [12] and spectroscopy [13-17] have appeared. Positive and negative ions formed by electron impact on BCl<sub>3</sub>, and their appearance potentials have been reported [8,10,18]. Negative ions in BCl<sub>3</sub> discharges have also been probed with optogalvanic spectroscopy [19], and mass spectrometry [7,9].

Despite the technological interest in this molecule, and the many papers on its chemistry in plasmas, the cross sections for electron impact ionization of BCl<sub>3</sub> and the gas-phase ion-molecule reactions of

its charged fragments have not been reported. We have quantified these collisional cross sections by Fourier transform mass spectrometry (FTMS), as we have reported previously for tetramethylsilane [20], tetraethylorthosilicate [21], and silane [22].

### 2. Experimental

Boron trichloride (BCl<sub>3</sub>, 99.9%, Aldrich) was diluted with Argon (99.999% Matheson Research Grade) in a ratio of 50:50 and admitted through a precision leak valve into a modified Fourier-transform mass spectrometry (FTMS) system that has been described in detail elsewhere[23]. In brief, ions are formed by electron impact in a cubic ion cyclotron resonance (ICR) trap cell at pressure in the  $10^{-7}$  Torr range. An electron gun (Kimball Physics ELG2, Wilton, NH) irradiates the trap with a few hundred picoCoulombs of low-energy electrons. The ions' motions are constrained radially by a superconducting solenoidal magnetic field of  $\approx$  2 T and axially by a

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nominal ( $\approx$  2 V) electrostatic potential applied to the trap faces that are perpendicular to the magnetic field. Ions of all mass-to-charge ratios are simultaneously and coherently excited into cyclotron orbits using a radiofrequency voltage applied to two opposing trap faces that are parallel to the magnetic field [24,25]. Following cyclotron excitation, the image currents induced on the two remaining faces of the trap are amplified, digitized, and Fourier analyzed to yield a mass spectrum.

Calculation of cross sections from the mass spectrum requires knowledge of the gas pressure, the electron beam current, and the number of ions produced. These calibration issues have been described previously [23,26]. The ratio of  $BCl_x^+$ ,  $Cl^+$ :  $Ar^+$  signals gives cross sections relative to the well-known cross sections for argon [27,28] ionization since the BCl<sub>3</sub>: Ar pressure is known. As a cross-check, and for ionmolecule kinetic analyses, the gas pressure is calibrated using a pulsed valve and a spinning rotor friction gauge (MKS Instruments model SRG2, Burlington, MA) with the vacuum chamber isolated from the pumps by closed gate valves. Electron current is collected on a Faraday cup and recorded with a digital oscilloscope after passage of the electron beam through the ion trap. The quantitative relationship between the image current and the number of ions is based on a lengthy, but elementary, solution of Maxwell's equations for the cubic ICR cell. This is required to quantify both excitation of the ions and detection of the resulting image current [23].

The distribution of electron energies in the trap, based on solution of Laplace's equation for the experimental geometry, is roughly Gaussian with a full width at half maximum of 0.5 eV due to the electrostatic trapping bias [23]. The energy scale is accurate to  $\pm 0.5$  eV based on comparison of noble gas ionization thresholds with spectroscopic data. We fit the cross-section data to a heuristic but parsimonious functional form:

$$\sigma(\epsilon - T) = A \times \tanh \frac{\pi * (\epsilon - T)}{\alpha} \times e^{-k(\epsilon - T)}$$
,

where  $\sigma$  is the cross section,  $\epsilon$  is the electron energy, T is the appearance potential, A scales the amplitude, k characterizes the higher energy behavior of  $\sigma$ , and  $\alpha$  quantifies  $d\sigma/d\epsilon$  near threshold.

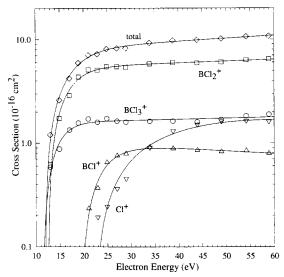


Fig. 1. Cross sections (cm<sup>2</sup>) for ionization of BCl<sub>3</sub> by electron impact. Points represent experimental data. Solid lines are fits of the equation described in the text.

#### 3. Results and discussion

Ionization cross-sections for BCl3 are shown in Fig. 1, while parameters for functional fits to the observed cross-sections are summarized in Table 1. A striking feature of the data is the observation of the molecular ion, BCl<sub>3</sub><sup>+</sup>, in substantial yield. In a recent paper on ionization in plasmas containing BCl<sub>3</sub> [7], no BCl<sub>3</sub><sup>+</sup> in the amplitude modulated discharge mass spectra was reported. We conclude that the BCl<sub>3</sub> has been substantially consumed by reactions with electrons, ions, surfaces, and neutral radicals during the long residence time of the gas in these plasmas. This conclusion is reinforced by the absence of B<sup>+</sup> in the FTMS spectra of BCl<sub>3</sub> and its presence in the amplitude modulated plasma spectra shown in reference [7]. We ascribe the observation of B<sup>+</sup> to dissociative ionization of species other than BCl<sub>3</sub> that are produced in the radiofrequency discharge [7].

The present results also update the observations in reference [8] where both  $B^+$  and  $Cl_2^+$  were reported in the mass spectra of  $BCl_3$ . The above work correctly attributed the formation of the latter to an artifact of pyrolysis on the ionizer filament. The present data show neither  $B^+$  nor  $Cl_2^+$  because pyrolysis is precluded by the 2 meter distance between the filament and ion trap. We propose that the observation of  $B^+$  in reference [8] is likewise a consequence of filament pyrolysis.

Table 1
Fitting parameters for simple and dissociative ionization cross sections. Also shown are appearance potentials estimated from thermochemical data in the JANAF tables

Ion	A (cm <sup>2</sup> )	k (eV <sup>-1</sup> )		T (eV)	JANAF T (eV)
BCl <sub>3</sub> <sup>+</sup>	$1.6 \times 10^{-16}$	$-2.4 \times 10^{-3}$	15	11.4	11.6
	$5.3 \times 10^{-16}$	$-3.8 \times 10^{-3}$	21	12.5	12.4
	$1.0 \times 10^{-16}$	$5.9 \times 10^{-3}$	24	19.4	19.5
$Cl^+$	$2.4\times10^{-16}$	$6.7\times10^{-3}$	80	22.3	26.7

The most abundant positive ion from threshold to 60 eV is  $BCl_2^+$ . By introducing a time delay between ion formation at 25 eV and ion cyclotron excitation and detection, we track the reactions of ion fragments with  $BCl_3$  as shown in Fig. 2. The more extensively dissociated ions  $BCl^+$  and  $Cl^+$  react with  $BCl_3$  to produce  $BCl_2^+$  at rates of  $5.3\pm0.5$  and  $6.2\pm0.5\times10^{-10}$  cm<sup>3</sup>s<sup>-1</sup>, respectively. The  $Ar^+$  ion also reacts rapidly:

$$Ar^{+} + BCl_{3} \rightarrow BCl_{2}^{+} + (Ar, Cl)$$
  
 $k = 5.0 \pm 0.5 \times 10^{-10} \text{ cm}^{3} \text{ s}^{-1}.$ 

Based on the published value for the polarizability of BCl<sub>3</sub>,  $\alpha = 9.38 \times 10^{-24}$  cm<sup>3</sup> [29], these reactions occur at about one-half of the Langevin limiting value. The reaction rates of BCl<sub>x</sub><sup>+</sup> with BCl<sub>3</sub> are the same whether the ions were formed by 25 eV or 50 eV electron impact. The depletion of Cl<sup>+</sup> is about 1.5 times faster at 50 eV, but our data cannot resolve whether this rate increase is attributable to spin-orbit, electronic, or translational excitation of the reactant Cl<sup>+</sup> ion at 50 eV.

Small quantities of HCl are observed, either from impurities in the BCl<sub>3</sub> cylinder, or as products of the reaction between BCl<sub>3</sub> and traces of water in the vacuum manifolds. We also observe the production of BClOH<sup>+</sup> that arises either from reaction of water vapor with BCl<sub>3</sub><sup>+</sup>:

$$BCl_3^+ + H_2O \rightarrow BClOH^+ + (H, 2Cl)$$

or dissociative charge transfer to hydrolyzed BCl<sub>3</sub>:

$$\begin{split} BCl_3 + H_2O &\rightarrow BCl_2OH + HCl, \\ (Ar^+, BCl_3^+) + BCl_2OH &\rightarrow BClOH^+ + Cl \\ &+ (Ar, BCl_3). \end{split}$$

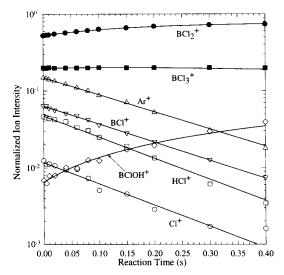


Fig. 2. Time evolution of positive ion species produced by 25 eV electron impact at a BCl<sub>3</sub> pressure of  $3.2 \times 10^{-7}$  Torr. Traces of HCl<sup>+</sup> are attributed to the reaction of BCl<sub>3</sub> with background water vapor. Points represent experimental data. Solid lines are fits of a kinetic model which gives the reaction rate coefficients presented in the text.

No BCIOH<sup>+</sup> was observed in kinetic experiments during which all ions but BCl<sub>2</sub><sup>+</sup> were ejected.

Negative ions from electron attachment to BCl<sub>3</sub> were first examined between 10 and 60 eV. No anions attributable to direct dissociative attachment at these energies were observed. However, secondary electrons from positive ionization were trapped in the ICR cell, and these electrons produced substantial quantities of Cl<sup>-</sup> and Cl<sub>2</sub>. No boron-containing anions were observed by the secondary electron attachment.

In order to study dissociative attachment of electrons to BCl<sub>3</sub> at energies below 10 eV, we studied the negative ion intensities as a function of applied trapping potential. The results are shown in Fig. 3 at a primary electron energy of 50 eV. We note that the range of secondary electron energies in the trap is constrained both by their kinetic energy following ionization and by the applied trapping potential. As the trapping potential increases the mean energy of trapped secondary electrons rises, leading to increased dissociative attachment as shown in Fig. 3. We infer that the secondary electrons from positive ionization were trapped in the ICR cell, and dissociative attachment by these electrons produced substantial quantities of Cl<sup>-</sup>

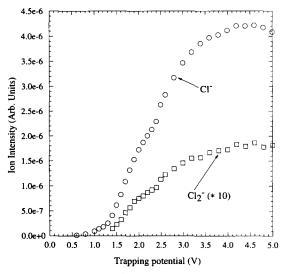


Fig. 3. Negative ion yields from trapped secondary electrons as a function of the applied trap bias. The primary electron energy is 50 eV.

and Cl<sub>2</sub><sup>-</sup>. The above conclusion is reinforced by the observation of negative ion production after cessation of the electron beam, as shown in Fig. 4. Although the energy resolution of our experiment is inferior to that of conventional crossed beam measurements for electron energies below 10 eV, we identify the low-energy attachment resonances and their product ions by FTMS.

Due to uncertainties in the number and in the energy distribution of trapped secondary electrons, the data summarized in Fig. 4 do not permit derivation of the rate coefficients for negative-ion molecule reactions. However, the data do reveal three features of anion chemistry in  $BCl_3$ . First,  $Cl_2^-$  reacts rapidly with  $BCl_3$ :

$$Cl_2^- + BCl_3 \rightarrow BCl_4^- + Cl$$

but the rate for the Cl<sup>-</sup> reaction:

$$Cl^- + BCl_3 \rightarrow BCl_4^-$$

is substantially slower. At present we cannot say whether the product  $BCl_4^-$  (from the latter reaction) is stabilized by emission of radiation or by a combination of a long vibrational lifetime and collisional quenching at  $\approx 10^{-6}$  Torr. Second, the ion-molecule reaction:

$$Cl^- + BCl_3 \rightarrow Cl_2^- + (B, 2Cl)$$

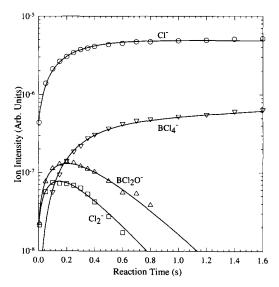


Fig. 4. Negative ion yields as a function of time delay between the generation of secondary electrons in the trap and the observation time. The increase in ion concentration over the first  $\approx 400$  ms is due to the attachment of trapped secondary electrons.

is not observed, indicating that  $\operatorname{Cl}_2^-$  is produced only by the dissociative attachment of electrons to  $\operatorname{BCl}_3$ . Both  $\operatorname{Cl}^-$  and  $\operatorname{Cl}_2^-$  were reported in drift-dwell-drift electron swarm experiments [18] but later quadrupole mass spectrometry of  $\operatorname{BCl}_3$  plasmas reported only  $\operatorname{Cl}^-$  [9]. Finally, the data in Fig. 4 show that  $\operatorname{BCl}_2\operatorname{O}^-$  is formed by dissociative attachment to an impurity neutral such as  $\operatorname{BCl}_2\operatorname{OH}$ , rather than by a negative-ion molecule reaction. The formation of  $\operatorname{BCl}_2\operatorname{OH}$  is consistent with our observation of  $\operatorname{BCl}_2\operatorname{OH}^+$  in the cation kinetics experiments, and with a mechanism by which  $\operatorname{BCl}_3$  is proposed to scavenge oxygen in discharges [30].

## 4. Conclusions

Electron impact ionization of BCl<sub>3</sub> yields BCl<sub>2</sub><sup>+</sup>, BCl<sub>3</sub><sup>+</sup>, BCl<sub>1</sub><sup>+</sup>, and Cl<sup>+</sup> with a total cross section of  $1.0\pm0.1\times10^{-15}$  cm<sup>2</sup> between 30 and 60 eV. Ion-molecule reactions of BCl<sup>+</sup> and Cl<sup>+</sup> yield BCl<sub>2</sub><sup>+</sup> with rate constants of  $5.3\pm0.5$  and  $6.2\pm0.5\times10^{-10}$  cm<sup>3</sup> s<sup>-1</sup>, respectively. Dissociative attachment of low-energy electrons to BCl<sub>3</sub> yields primarily Cl<sup>-</sup> with smaller quantities of Cl<sub>2</sub><sup>-</sup>. No boron-containing ions are found by dissociative attachment, but both Cl<sup>-</sup> and Cl<sub>2</sub><sup>-</sup> re-

act with BCl<sub>3</sub> to produce BCl<sub>4</sub>. No further clustering of BCl<sub>4</sub> is observed. We infer that heavier anions observed by mass spectrometric sampling from BCl<sub>3</sub> plasmas are a result either of attachment to higher molecular weight species formed in the plasma or to reactions of anions with neutral radicals that are precluded at the pressures and charge densities used in the FTMS experiments.

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#### References

- D.L. Flamm and V.M. Donnelly, Plasma Chem. Plasma Proc. 1 (1981) 317.
- [2] J.W. Coburn, Plasma Chem. Plasma Proc. 2 (1982) 1.
- [3] K.E. Greenberg, G.A. Hebner and J.T. Verdeyen, Appl. Phys. Lett. 44 (1984) 299.
- [4] L.E. Kline, in: Nonequilibrium effects in ion and electron transport, eds. J.W. Gallagher, D.F. Hudson, E.E. Kunhardt and R.J. Van Brunt (Plenum, New York, 1990).
- [5] A. Slaovi, F. Foulan, L. Fuchs, E. Foganassy and P. Siffert, Appl. Phys. A 50 (1990) 317.
- [6] R.A. Gottscho, Phys. Rev. A 36 (1987) 2233.
- [7] L.J. Overzet and L. Luo, Appl. Phys. Lett. 59 (1991) 161.
- [8] J. Marriott and J.D. Craggs, J. Electron. Control 3 (1957)
- [9] Z.Lj. Petrovic, W.C. Wang, M. Suto, J.C. Han and L.C. Lee, J. Appl. Phys. 67 (1990) 675.

- [10] I.S. Buchel'nikova, Sov. Phys. JETP 35 (1959) 783.
- [11] R. Nagpal and A. Garscadden, Appl. Phys. Lett. 64 (1994) 1626.
- [12] G.R. Scheller, R.A. Gottscho, T. Intrator and D.B. Graves, J. Appl. Phys. 64 (1988) 4384.
- [13] Z.J. Jabbour, K.E. Martus and K. Becker, Z. Phys. D 9 (1988) 263.
- [14] M. Suto, C. Ye, J.C. Han and L.C. Lee, J. Chem. Phys. 89 (1988) 6653.
- [15] L.C. Lee, J.C. Han and M. Suto, J. Chem. Phys. 91 (1989) 2036
- [16] P.G. Gilbert, R.B. Siegel and K. Becker, Phys. Rev. A 41 (1990) 5594.
- [17] F.W. Breitbarth, Plasma Chem. Plasma Proc. 12 (1992) 261.
- [18] J.A. Stockdale, D.R. Nelson, F.J. Davis and R.N. Compton, J. Chem. Phys. 56 (1972) 3336.
- [19] R.A. Gottshco and C.E. Gaebe, IEEE Trans. Plasma Sci. PS-14 (1986) 92.
- [20] S. McGinnis, K. Rielh and P.D. Haaland, Chem. Phys. Lett. 232 (1994) 99.
- [21] J. Holtgrave, K. Riehl, D. Abner and P.D. Haaland, Chem. Phys. Lett. 215 (1993) 548.
- [22] P.D. Haaland, J. Chem. Phys. 93 (1990) 4066.
- [23] K. Riehl, Collisional detachment of negative ions using FTMS, Ph.D. Thesis, Air Force Institute of Technology (1992).
- [24] A.G. Marshall, T.L. Wang and T.L. Ricca, J. Am. Chem. Soc. 107 (1985) 7893.
- [25] S. Guan, J. Chem. Phys. 91 (1989) 775.
- [26] P.D. Haaland, Chem. Phys. Lett. 170 (1990) 146.
- [27] R.C. Wetzel, F.A. Baiocchi, T.R. Hays and R.C. Freund, Phys. Rev. A 35 (1987) 559.
- [28] E. Krishnakumar and S.K. Srivastava, J. Phys. B: At. Mol. Opt. Phys. 21 (1988) 1055.
- [29] R.C. Weast, ed., CRC Handbook of Chemistry and Physics, 66th Ed. (CRC Press, Boca Raton, 1985).
- [30] K. Tokunaga, F.C. Redeker, D.A. Danner and D.W. Hess, J. Electrochem. Soc. 128 (1981) 851.